



PATENT
Customer No. 22,852
Attorney Docket No. 08137.0004-00000

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)

Hiroshi SHINRIKI et al.)

Serial No.: 09/657,627)

Filed: September 8, 2000)

For: THIN FILM FORMING METHOD)
AND THIN FILM FORMING)
APPARATUS)

Group Art Unit: 1762

Examiner: B. Chen

#8/a
Hyda
12/30/01

Assistant Commissioner for Patents
Washington, DC 20231

Sir:

RECEIVED
DEC 27 2001
TC 1700

AMENDMENT

In reply to the Office Action dated June 20, 2001, the period for reply having been extended for three months by a request for extension and fee payment filed concurrently herewith, please amend the application as follows:

IN THE TITLE:

Please change the title to read ☒ METHOD OF FORMING A THIN FILM--.

IN THE CLAIMS:

Please cancel claim 7 without prejudice or disclaimer, amend claims 1-6, 8, and 9, and add new claims 12 and 13, as follows:

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✓ 1. (Amended) A method of forming a thin film on a substrate in a reactor comprising a side having a shower head with a plurality of nozzles and a separate discharge nozzle, the method comprising:

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